



AF/2829

PATENT
30205/37916

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of: Jae Hong Kim and
Sang Ick Lee

Serial No.: 10/038,375

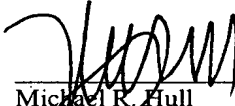
Filed: January 4, 2002

For: Chemical Mechanical Polishing
Slurry and Process for Ruthenium Films

Group Art Unit: 2829

Examiner: Asok K. Sarkar

I hereby certify that this paper and the documents referred to as enclosed therewith are being deposited with the United States Postal Service as first class mail, postage prepaid, on May 12, 2003, in an envelope addressed to Commissioner for Patents, P.O. Box 1450, Alexandria, Virginia 22313-1450


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AMENDMENT AFTER FINAL (37 C.F.R. § 1.116)

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Sir:

In response to the final office action mailed on February 14, 2003, please amend the above-referenced patent application as follows. Applicants respectfully submit that this amendment is in full compliance with Rule 116 because it raises no new issues and reduces the number of pending claims. The amendment also places the application in a better condition for appeal, if necessary.

Specifically, claims 2 and 4 have been canceled and the limitations thereof have been added to amended claim 1. Thus, the subject matter of amended claim 1 is identical to the subject matter of claim 4 as presented in the last amendment.

Finally, new claim 24 is a copy of claim 1 as presented in the previous amendment. Applicants respectfully submit that new claim 24 (or claim 1 as presented in the last amendment) is allowable over the prior art of record for the reasons set forth in the remarks section.

Therefore, applicants respectfully request that the Patent Office amend this application under Rule 116 as follows: